



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent Application Serial No. .... 10/643,680  
Filing Date ..... August 18, 2003  
Inventorship ..... Brenda D. Kraus et al.  
Assignee ..... Micron Technology, Inc.  
Group Art Unit ..... 1762  
Examiner ..... Brian K. Talbot  
Attorney's Docket No. .... MI22-2310  
Title: Atomic Layer Deposition Methods of Forming Conductive Metal Nitride  
Comprising Layers

**SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT**

References - See Attached Form PTO-1449

The attached form PTO-1449 is submitted in compliance with 37 CFR §1.56. No copies of any cited U.S. patents or U.S. published applications are included herewith. Copies of all other cited art are attached. No admission is made regarding whether all the submitted references are prior art.

Citation of these references is respectfully requested.

A check in the amount of \$180.00 is enclosed to cover the fee specified under 37 C.F.R. § 1.17(p).

Respectfully submitted,

Dated: 1-10-07

By:   
Mark S. Matkin  
Reg. No. 32,268

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Form PTO-1419		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. MI22-2310		SERIAL NO. 10/643,680	
<div style="position: relative; height: 100px;"> <div style="position: absolute; top: 0; left: 0; width: 100%; height: 100%; border: 2px solid black; border-radius: 50%; text-align: center; color: black; font-weight: bold; font-size: 1.2em;">             OPIE              JAN 10 2007              PATENT &amp; TRADEMARK OFFICE           </div> <div style="position: absolute; top: 50%; left: 50%; transform: translate(-50%, -50%); font-size: 0.8em;">             LIST OF ART CITED BY APPLICANT  <small>(use several sheets if necessary)</small> </div> </div>					APPLICANT: Kraus et al.			
					FILING DATE August 18, 2003		GROUP 1762	

  

U.S. PATENT DOCUMENTS							
*Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	6,203,613	03/01	Gates et al.			
	AB	10/196,814	07/02	Kyung-In			
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						

  

FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
	AJ						Yes      No
	AK						
	AL						

  

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
	AM		Park et al., "Plasma-Enhanced Atomic Layer Deposition of Tantalum Nitrides Using Hydrogen Radicals as a Reducing Agent", Electrochemical and Solid-State Letters, 4 (4) C17-C19, The Electrochemical Society, Inc. (2001).
	AN		
	AO		

  

EXAMINER	DATE CONSIDERED
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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